

Table 1

Experimental conditions of channel doping

with respect to the silicon-containing amorphous semiconductor film

substrate No.	chemical oxide film	diborane dilution ratio
1	None	0.1%B ₂ H ₆ /H ₂
2	Exist	0.1%B ₂ H ₆ /H ₂
3	None	1.0%B ₂ H ₆ /H ₂
4	Exist	1.0%B ₂ H ₆ /H ₂